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Tool Code	PROCESS	EQUIPMENT	MANUFACTURER	MODEL	WAFER SIZE	VINTAGE
07855	EPI	EPI	Applied Materials	Centura Epi	200	1995
09311	ETCH	DRY ETCHER	Applied Materials	Centura II DPS+ Metal	150	2001
09214	ION IMPLANT	IMPLANTER	Applied Materials	Quantum Leap	300	2007
07104	CVD	PLASMA CVD	ASM	Eagle10 TRIDENT	150	2007
09313	OTHERS	INSPECTION	CAMTEK	EAGLE-AP	150	2018
07888	PHOTOLITHO	STEPPER	Canon	FPA-3000EX6	200	2004
08293	RTP	RTA	Canon	HP-8800	200	2001
09244	PVD	SPUTTERING SYSTEM	CANON ANELVA	E-800S	-	-
09243	PVD	SPUTTERING SYSTEM	CANON ANELVA	E-800S	-	-
07426	PVD	SPUTTERING SYSTEM	CANON ANELVA	I-1060SV2 Plus1	200	2003
07837	DICING	DICER	DISCO	DFD6240	200	2004
07984	DICING	DICER	DISCO	DFD6340	200	-
09356	DICING	DICER	DISCO	DFD6361-2	300	2004
09212	PHOTOLITHO	COATER	EVG	EVG120	150/200	2015
07653	MARKING	Wafer Marker	GSI	MARK-EM	150	2002
07517	ETCH	ION MILLING	HITACHI	IML-6-1	150	1997
09259	ETCH	ION MILLING	Hitachi High-Tech	E-3500	-	2006
07960	METROLOGY	FIB	Hitachi High-Tech	FB-2100	-	2004
09265	METROLOGY	REVIEW SEM	Hitachi High-Tech	HD-2300	-	2004
09007	METROLOGY	REVIEW SEM	Hitachi High-Tech	HD-2300A	-	2007
07959	METROLOGY	REVIEW SEM	Hitachi High-Tech	HD2700B	-	2010
07852	METROLOGY	REVIEW SEM	Hitachi High-Tech	S-3400N	-	2010
09246	METROLOGY	REVIEW SEM	Hitachi High-Tech	SU1510	-	2009
09372	METROLOGY	REVIEW SEM	Hitachi High-Tech	SU1510	50/100/150	2016
09339	METROLOGY	REVIEW SEM	Hitachi High-Tech	SU3500	-	2018
07924	INSPECTION	VISUAL INSPECTION	INSPEC	LF2000	-	2005
07925	INSPECTION	VISUAL INSPECTION	INSPEC	LF2000	-	2005
07901	METROLOGY	FILM THICKNESS MEASUREMENT	JVS	JVX5200T	300	2005
09373	METROLOGY	DEFECT INSPECTION	KLA-Tencor	CandelaCS20V	50/100/150/200	2012
07878	METROLOGY	FILM THICKNESS MEASUREMENT	KLA-Tencor	OP3290	200	2004
07731	METROLOGY	STEP MEASURING SYSTEM	KLA-Tencor	P-11	100～200	2001
07929	METROLOGY	STEP MEASURING SYSTEM	KLA-Tencor	P-15	150～300	2004
09252	METROLOGY	WAFER PARTICLE COUNTER	KLA-Tencor	SP1-DLS	200	2005
09218	METROLOGY	WAFER PARTICLE COUNTER	KLA-Tencor	SP1-TBI	200/300	2001
07883	FURNACE	FURNACE_DIFFUSION	KOKUSAI ELECTRIC	DD-812V(N2 Anneal)	150	2007
07420	FURNACE	FURNACE_LP-CVD	KOKUSAI ELECTRIC	DJ-1206V-DF(ULT/SiO2)	300	2007
09061	CVD	CVD	Lam Research	CONCEPT ONE	125	1998
07956	ETCH	OXIDE ETCHER	Mattson	ASPEN2-ICP-LE	200	1997
07992	ETCH	OXIDE ETCHER	Mattson	ASPEN2-RTA	200	1999
09052	WET	CLEANING SYSTEM	Mimasu	MSC-4000H	200	2005
09267	WET	CLEANING SYSTEM	Mimasu	MSE-3000Mi/MSP-2Mi	200	2006
09323	PHOTOLITHO	STEPPER_i-Line	Nikon	NSR2205i11C	150	1997
09149	PHOTOLITHO	STEPPER_i-Line	Nikon	NSR-2205i11D	100	1995
09326	PHOTOLITHO	STEPPER_i-Line	Nikon	NSR2205i12D	150	1999
07913	METROLOGY	MICROSCOPE	OLYMPUS	MX61L-F	-	2006
09053	ETCH	DRY ETCHER	Panasonic	E748SC	200	2006
07979	METROLOGY	AUTOMATIC VISUAL INSPECTION	RUDOLPH	AXi-935	200	-
09349	WET	POST CMP CLEANING SYSTEM	SCREEN	AS2000	200	2000
09352	WET	POST CMP CLEANING SYSTEM	SCREEN	AS2000	200	2000
09272	METROLOGY	FILM THICKNESS MEASUREMENT	SCREEN	VM-3210	150-300	2012
09208	ASHER	ASHER	SHIBAURA	µASH300	300	2004
09345	ION IMPLANT	IMPLANTER_HIGH CURRENT	SMIT	LEX	200	2007

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Tool Code	PROCESS	EQUIPMENT	MANUFACTURER	MODEL	WAFER SIZE	VINTAGE
09346	ION IMPLANT	IMPLANTER_HIGH CURRENT	SMIT	LEX3-M	300	2006
09344	ION IMPLANT	IMPLANTER_MEDIUM CURRENT	SMIT	MC3-CE	300	2005
09343	ION IMPLANT	IMPLANTER_MEDIUM CURRENT	SMIT	MC3-FOUP	300	2000
09330	ION IMPLANT	IMPLANTER_HIGH CURRENT	SMIT	NV-GSDⅢ-180	150	2003
09216	ION IMPLANT	IMPLANTER	SMIT	NV-GSDⅢ-90	125	2000
09348	ION IMPLANT	IMPLANTER_HIGH CURRENT	SMIT	NV-GSDⅢ-LE	200	2003
09331	ION IMPLANT	IMPLANTER_HIGH ENERGY	SMIT	NV-GSD-HE	150	2000
07990	ION IMPLANT	IMPLANTER_MEDIUM CURRENT	SMIT	NV-MC3	200	2001
09347	ION IMPLANT	IMPLANTER_HIGH CURRENT	SMIT	SHX/ⅢS	300	2014
09334	PHOTOLITHO	COATER&DEVELOPER	TEL	ACT8	200	1999
09099	PHOTOLITHO	COATER&DEVELOPER	TEL	Lithius i+	300	2005
07624	PHOTOLITHO	COATER	TEL	MARK-8	200	1996
09304	PHOTOLITHO	COATER	TEL	MARK-8	150	1992
07623	PHOTOLITHO	COATER&DEVELOPER	TEL	MARK-8	200	1998
09305	PHOTOLITHO	DEVELOPER	TEL	MARK-8	150	1993
07816	WET	WAFER SCRUBBER	TEL	SS-4	200	2003
09381	WET	WAFER SCRUBBER	TEL	SS-4	200	2000
09210	ETCH	OXIDE ETCHER	TEL	Telius SCCM	300	2004
07889	ETCH	OXIDE ETCHER	TEL	UnityIIe-655PP	150	2000
09082	Vapor Deposition	Vapor Deposition	ULVAC	EBX-1000C	150	2006
09242	PVD	EVAPORATOR	ULVAC	ei-5	76.2/100	-
09083	Vapor Deposition	Vapor Deposition	ULVAC	EX-550-C10	150	1994
09241	ETCH	DRY ETCHER	ULVAC	NE-550EX	100	-
09200	PVD	SPUTTERING SYSTEM	ULVAC	SRH-420	200	2006
09100	PVD	SPUTTERING SYSTEM	ULVAC	SRH-530	100	2013
09379	IMPLANT	MEDIUM CURRENT ION IMPLANTER	VARIAN	E-500HP	200	1995
09380	IMPLANT	MEDIUM CURRENT ION IMPLANTER	VARIAN	VIISION80	200	1996

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